## Current–Voltage, Capacitance–Voltage–Temperature, and DLTS Studies of Ni|6*H*-SiC Schottky Diode

© A. Rabehi<sup>1,2</sup>, B. Akkal<sup>1</sup>, M. Amrani<sup>1</sup>, S. Tizi<sup>1</sup>, Z. Benamara<sup>1</sup>, H. Helal<sup>1</sup>, A. Douara<sup>2</sup>, B. Nail<sup>2</sup>, A. Ziane<sup>1</sup>

 <sup>1</sup> Laboratoire de Micro-électronique Appliquée. Université Djillali Liabés de Sidi Bel Abbés, BP 89, 22000, Sidi Bel Abbés, Algeria
<sup>2</sup> Institute of Science and Technology, Tissemsilt University Center, 38000 Tissemsilt, Algeria

E-mail: rab\_ehi@hotmail.fr

Received October 12, 2020 Revised October 12, 2020 Accepted for publication December 10, 2020

In this paper, we give a systematical description of Ni|6H-SiC Schottky diode by current–voltage I(V) characteristics at room temperature and capacitance–voltage C(V) characteristics at various frequencies (10-800 kHz) and various temperatures  $(77-350^{\circ}\text{K})$ . The I(V) characteristics show a double-barrier phenomenon, which gives a low and high barrier height ( $\phi_{bn}^{L} = 0.91 \text{ eV}$ ,  $\phi_{bn}^{H} = 1.55 \text{ eV}$ ), with a difference of  $\Delta \phi_{bn} = 0.64 \text{ eV}$ . Also, low ideality factor  $n^{L} = 1.94$  and high ideality factor  $n^{H} = 1.22$  are obtained. The C-V-T measurements show that the barrier height  $\phi_{bn}$  decreases with decreasing of temperature and gives a temperature coefficient  $\alpha = 1.0 \cdot 10^{-3} \text{ eV/K}$  and  $\phi_{bn}(T = 0 \text{ K}) = 1.32 \text{ eV}$ . Deep-level transient spectroscopy (DLTS) has been used to investigate deep levels in the Ni|6H-SiC Schottky diode. The traps signatures such as activation energies  $E_a = 0.50 \pm 0.07 \text{ eV}$ , capture cross-section  $\sigma = 1.8 \cdot 10^{-20} \text{ cm}^2$ , and defect concentration  $N_{\rm T} = 6.2 \cdot 10^{13} \text{ cm}^{-3}$  were calculated from Arrhenius plots.

Keywords: sillicon carbide, Schottky diodes, I-V, C-V-T, deep-level transient spectroscopy (DLTS).

Full text of the paper will appear in journal SEMICONDUCTORS.